

Superfine Flip-Chip Interconnections in 20- μm -pitch

Manabu Bonkohara

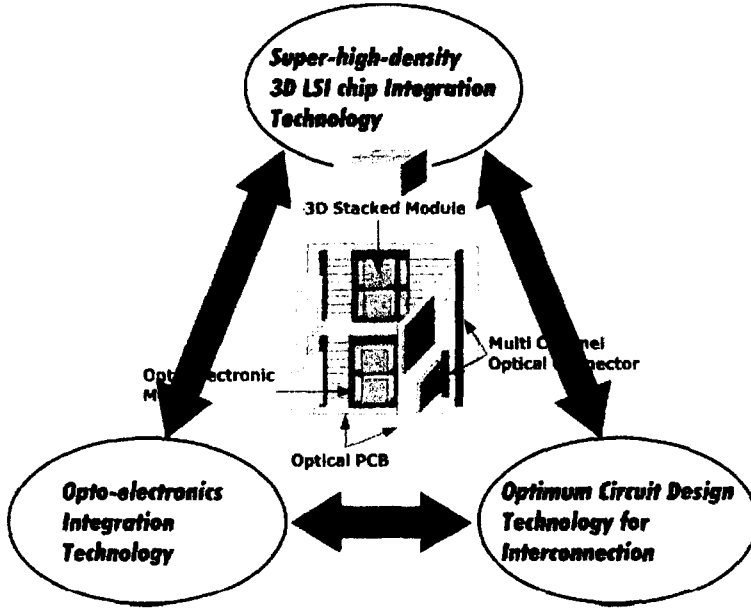
Electronics System Integration Dept.
ASET

10/20/01 1.0.0/ASET

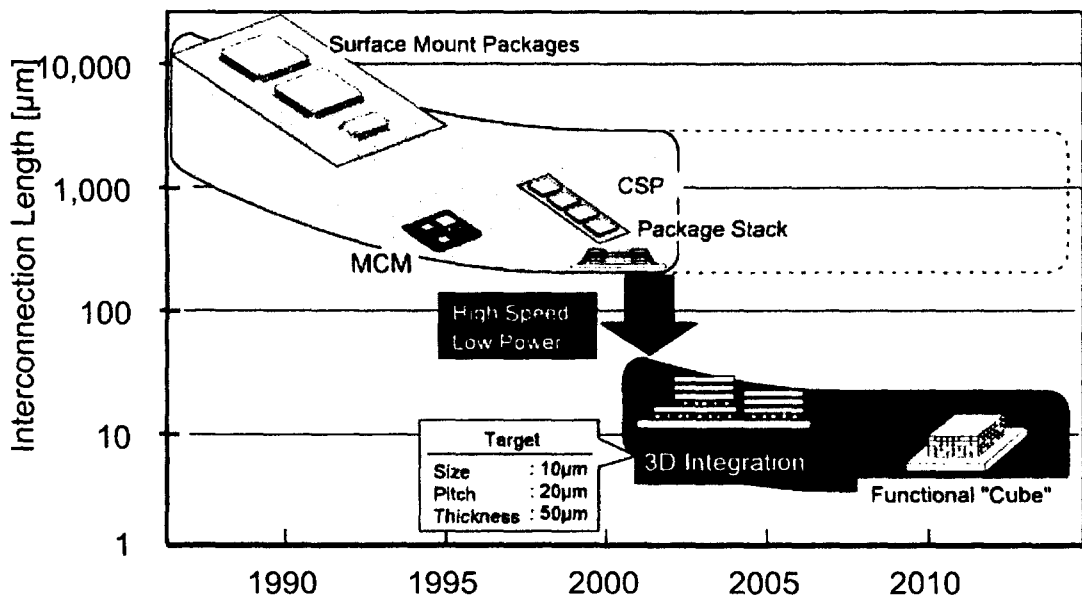
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- Introduction
 - Background and abstract of our development
- Performance of 20- μm -pitch bonding
 - Reliability of flip-chip Au-Au bonding
- Low temperature interconnection
 - Ultrasonic flip-chip bonding
 - Cu bump bonding
- Summary

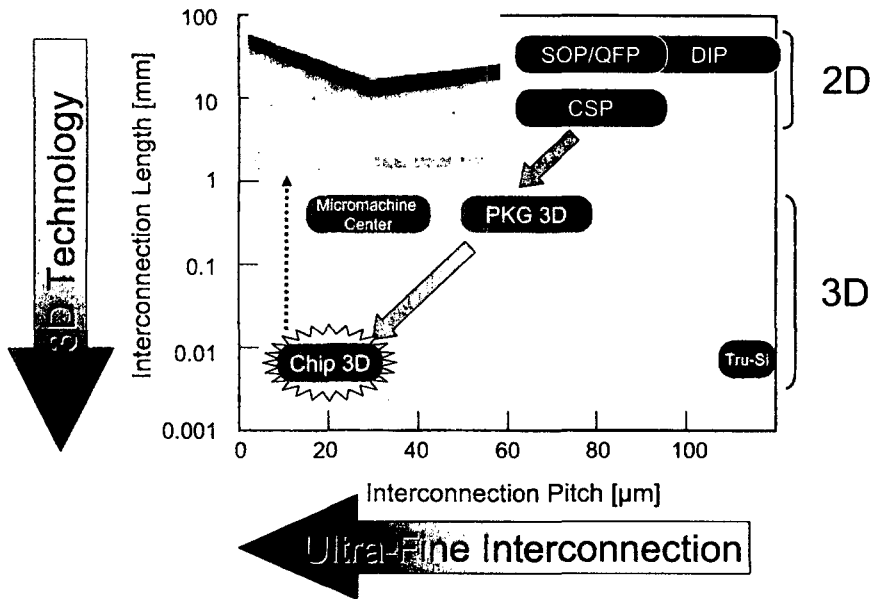
E-SI Research Scheme



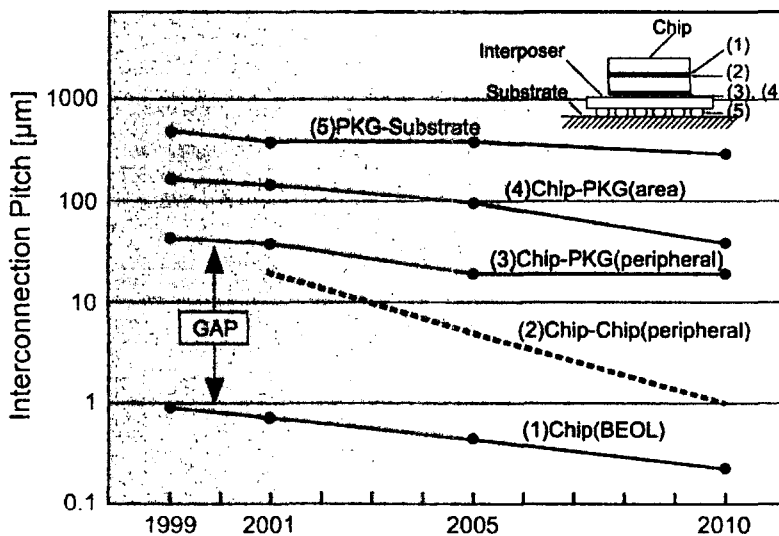
Packaging Trend



Important Factors



Hierarchy of Design Rules of Interconnection

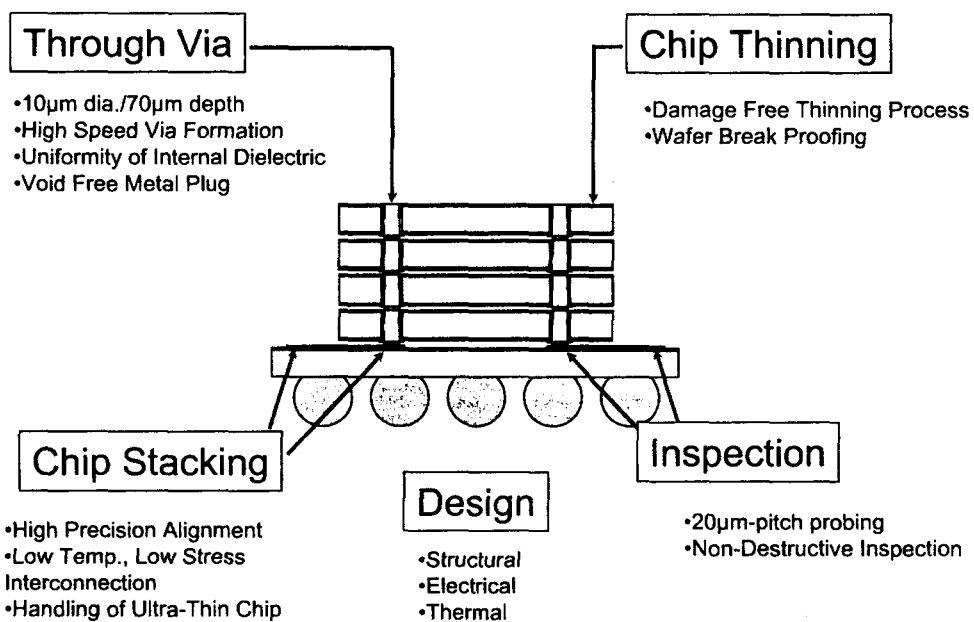


Development Schedule

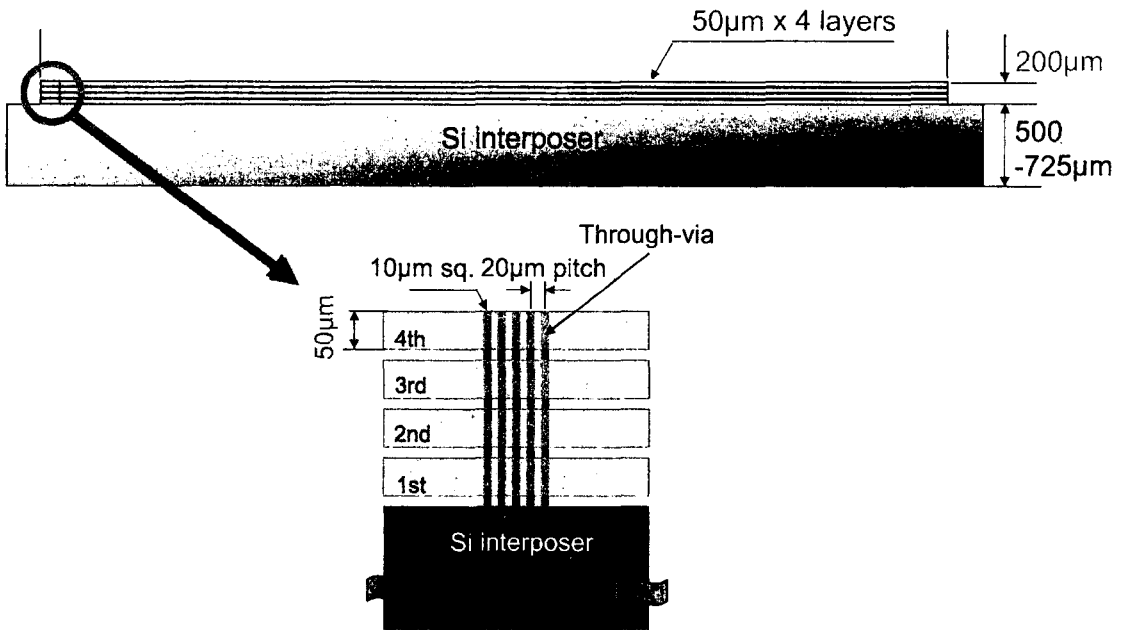
(FY)

1999	2000	2001	2002	2003
	Structure/Process Development	Brush Up		
	Defining 3D Structure and Process Flow	Sample Build & Performance Check	3D-OE Development	Total Integration
			Unit Technology & Interface	Integration & Brush Up
	Application Images of 3D Technologies		High Speed Memory Module	
			System on Package (SoP)	
			Ultra-High Density Interposer	

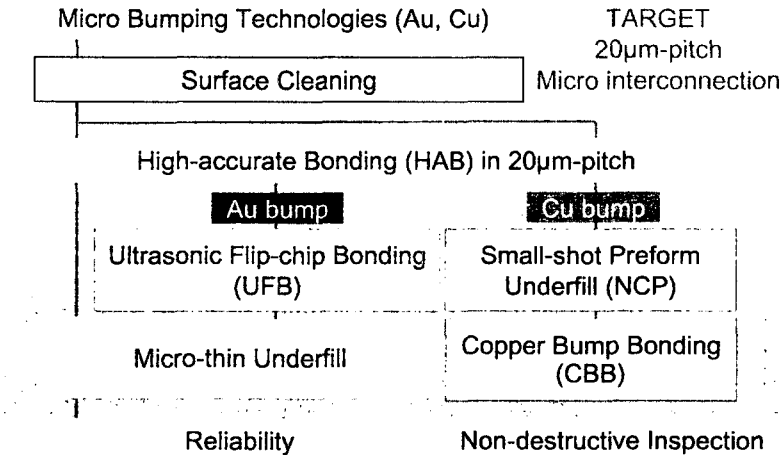
Technology Map



Structure of the 3D Module



Chip Stacking Technology Map



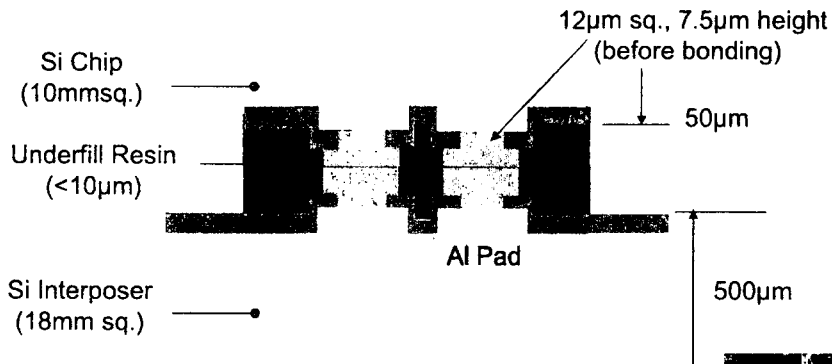
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Reliability of flip-chip Au-Au bonding

- Purpose
 - Interconnection reliability of 20- μm -pitch flip-chip bonding.
 - Effect of CTE of underfill resin.
- Methods
 - Chip-on-chip (COC) structure.
 - Three kinds of filler content.
 - -40°C to 125°C, up to 1500 cycles. Electrical tests of daisy-chain circuits.
 - Failure analysis and simulation.

Experimental model



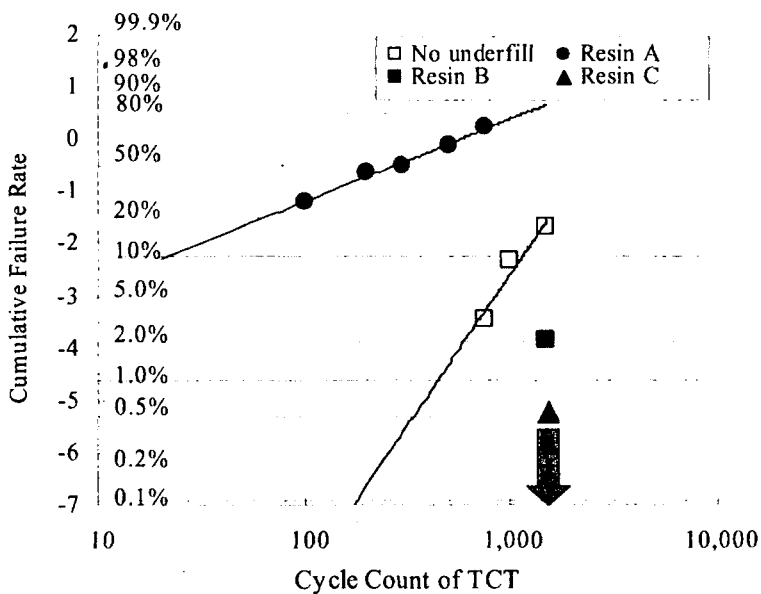
Bonding Condition: 24.5 N, 7 s, 350 °C
 Underfill Cure Temp.: 80 °C



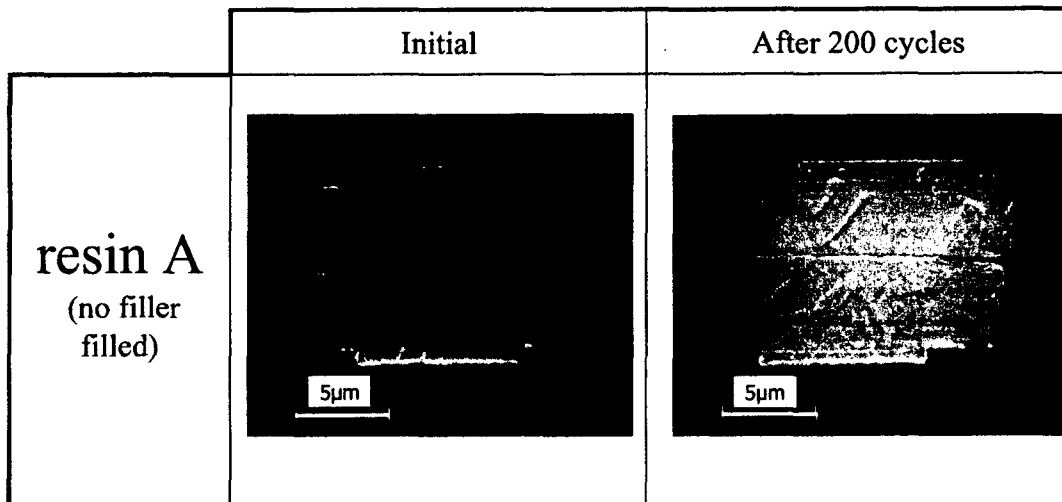
Material Properties of Underfill Resin

	Unit	Resin A	Resin B	Resin C
Filler Contents	wt %	0	50	60
Elastic Modulus	GPa	3.2	6.0	8.5
Tg	°C	136	136	134
CTE (<Tg)	ppm/°C	71	41	33
CTE (>Tg)	ppm/°C	192	103	106

Reliability Test Results

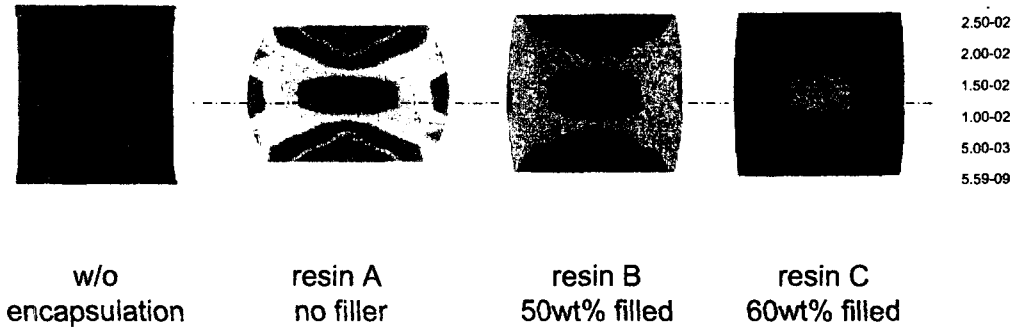


Failure Analysis Results

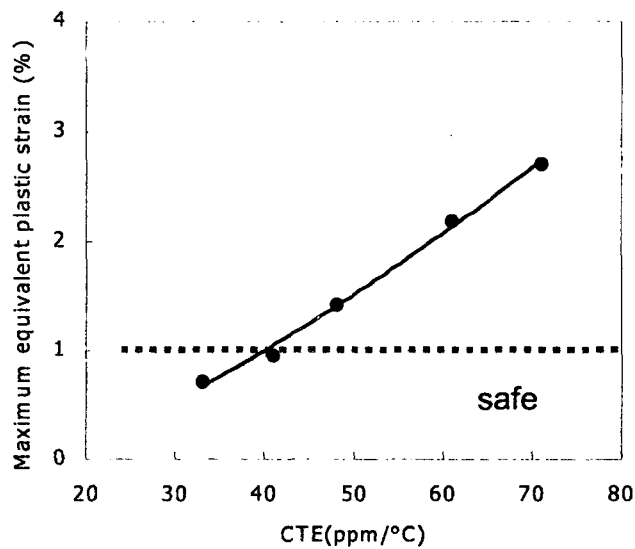


Results of FEM Analysis

Maximum Plastic Equivalent Strain



Maximum Plastic Equivalent Strain



Contents

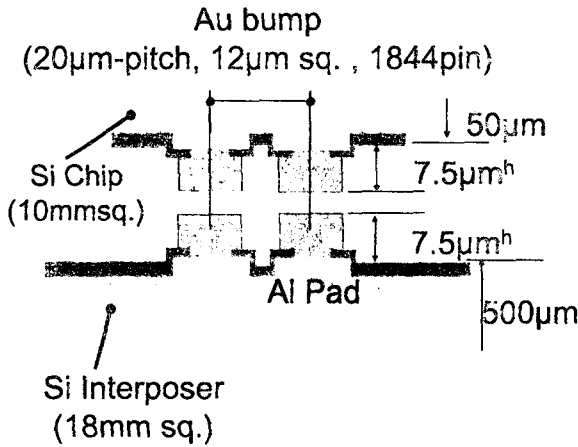
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Ultrasonic Flip-chip Bonding

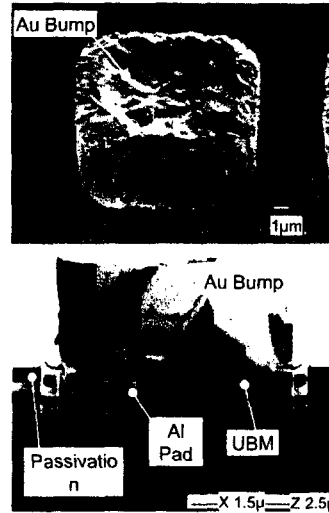
- Purpose
 - Basic evaluation of ultrasonic flip-chip bonding (UFB) of 20- μm -pitch bumps.
- Methods
 - Chip-on-chip structure.
 - Positional accuracy.
 - Electrical test with daisy chain circuits.
 - Chip damage check.
 - Micro-analysis of bonding interface.

COC Structure for 20 μ m-pitch Interconnections

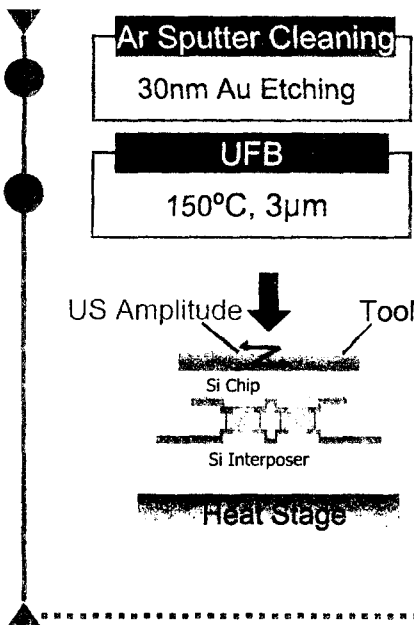
■ COC Structure



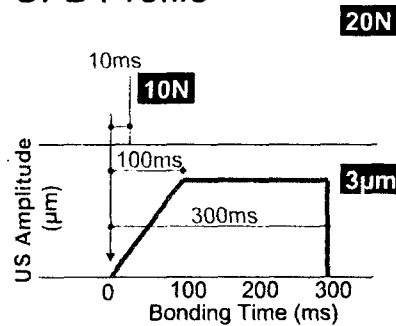
■ 20 μ m-pitch Au Bump



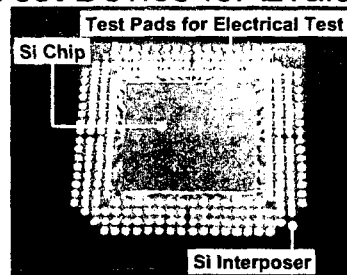
UFB Conditions



■ UFB Profile

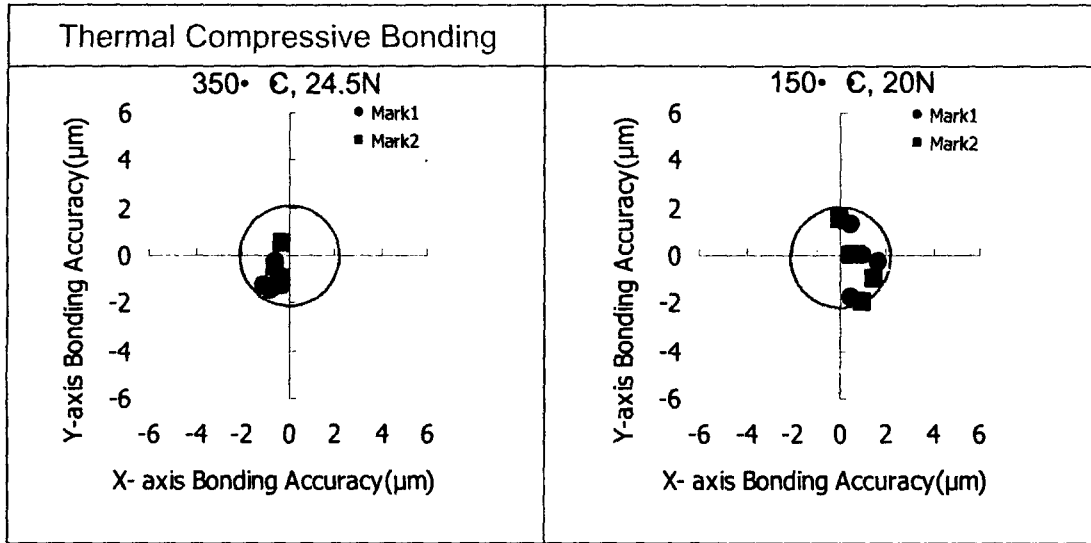


■ Test Device for Evaluation



UFB Bonding Accuracy

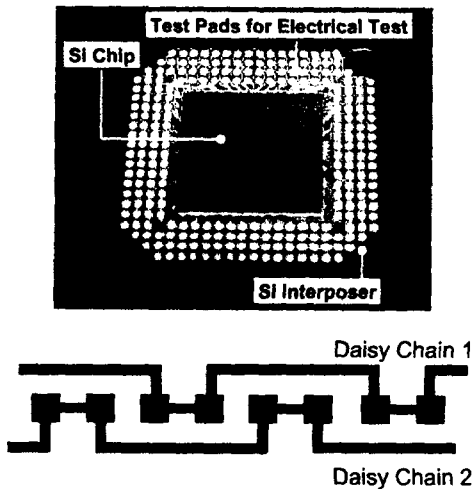
Positional Tolerance Data



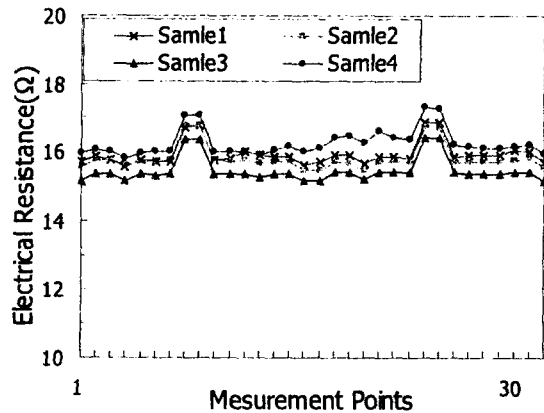
↓UFB bonding accuracy was confirmed within $\pm 2\mu\text{m}$.

UFB Connection Resistance

Daisy chain Pattern



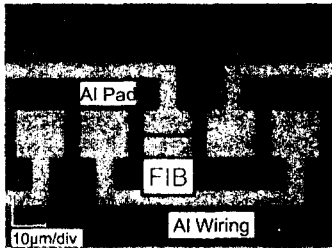
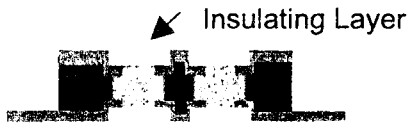
Electrical Resistance Data



↓UFB connection resistance was stable.

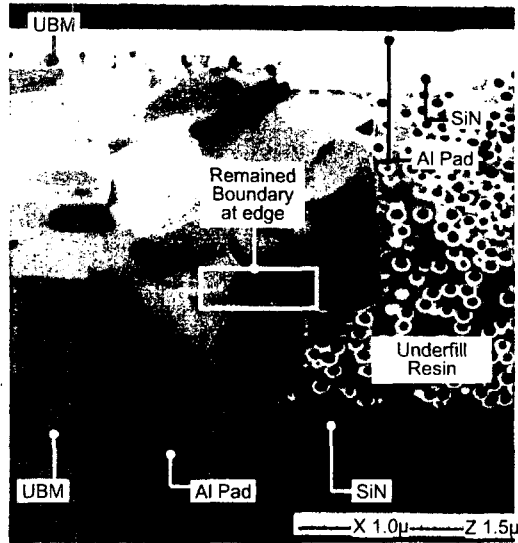
UFB Damage & Bondability

After Si Etching



Back Side of Al Pad

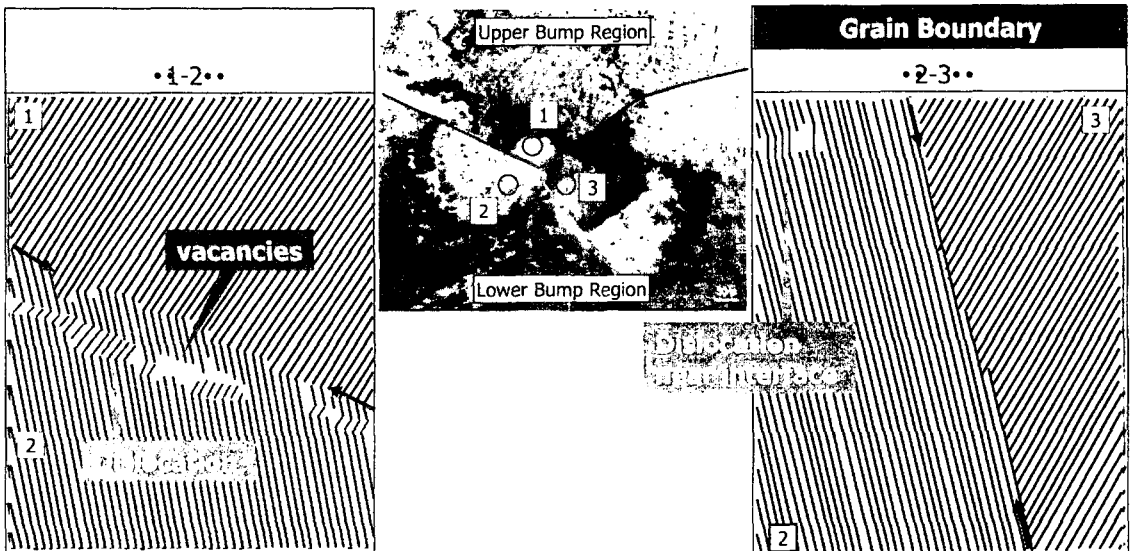
FIB Analysis



Cross section of interconnection

↓No remarkable damage by UFB was observed.

TEM Image & Lattice Pattern



↓The solid phase bonding interface was discontinuous boundary with some dislocations and vacancies.

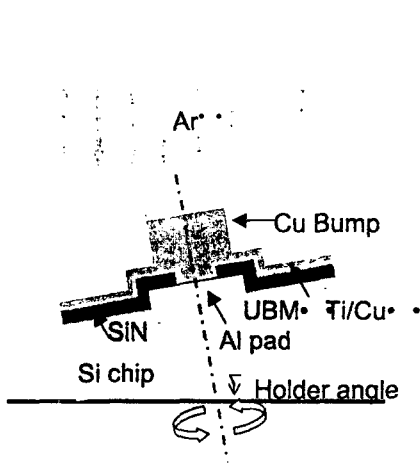
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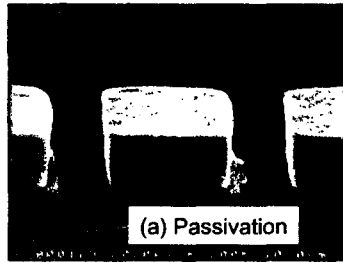
Copper Bump Bonding

- Purpose
 - Basic evaluation of dry process applicability to under bump metallurgy (UBM) removal.
- Methods
 - Application of ion milling.
 - Analysis of residues around bumps.

Dry Processes Applied to UBM Removal

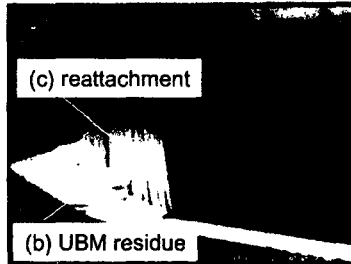


Ion Milling to Bumped Wafer



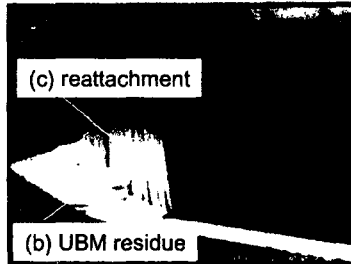
(a) Passivation

Si & N were detected.



(b) UBM residue

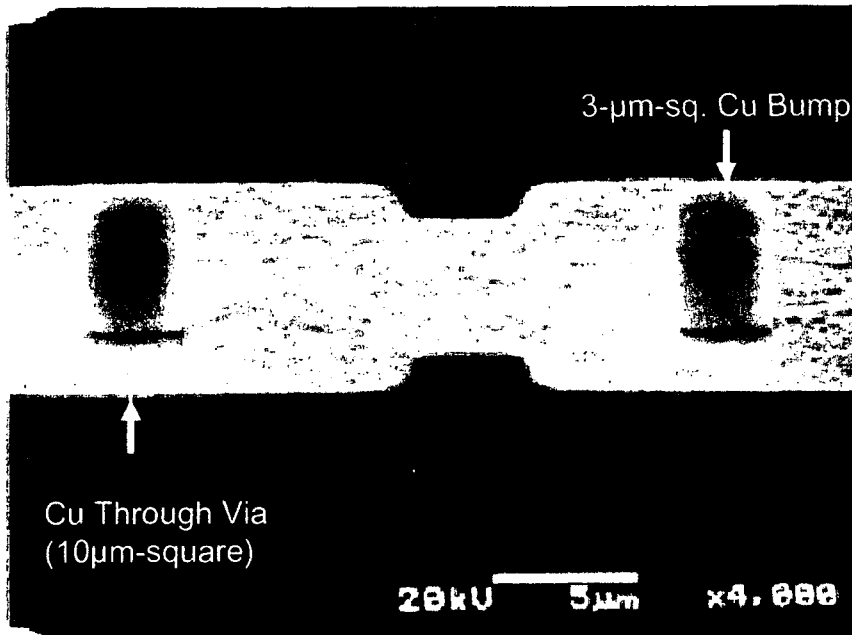
Ti was detected.



(c) reattachment

Ti was detected.
(small amount)

SEM Micrograph of Cu Bumps



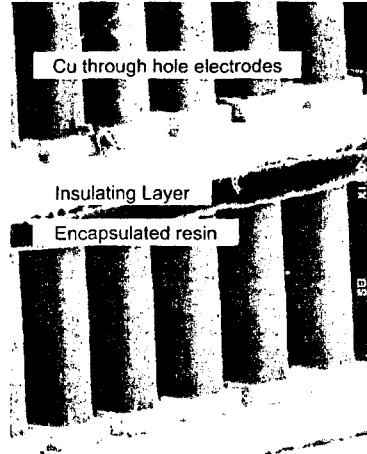
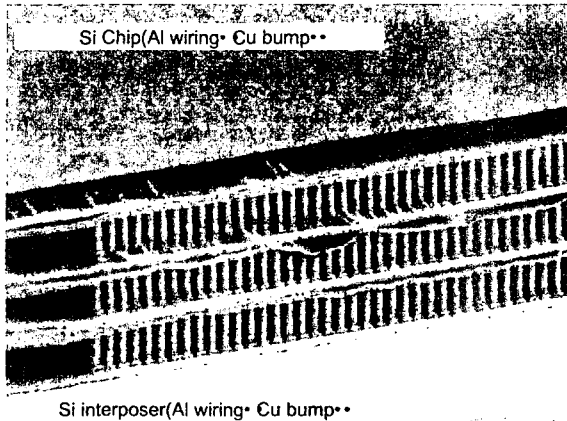
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Summary

- Reliability
 - The reliability strongly depended on the CTE of underfill resin.
 - The fractured portion was identical with the maximum plastic equivalent strain.
 - 1% or less value of the maximum plastic equivalent strain certified more than 1000 cycle of TCT life.
- UFB
 - Bonding accuracy was confirmed within $\pm 2\mu\text{m}$.
 - The fundamental bondability of UFB was confirmed with no damage around aluminum pads.
 - Some dislocations and vacancies were observed at the interface, however, the atomic level bonding was confirmed.
- CBB
 - Dry process was applied to UBM removal.

Four Layer Stacked Structure with 20μm-pitch



Acknowledgement

This work was performed under the management of ASET in the basic plan of Research and Development on Ultra High-Density Electronics System Integration supported by NEDO.

